

| | Hits | Search Text | DBs |
|----|------|--|---|
| 28 | 1 | 430/324.ccls. and ((substrate or wafer) same (barrier or layer or coat\$4 or film) same ((polyphenol\$4 near6 polymer\$4) or novolac) same (resist or photoresist or photosensitive)) and (expos\$4 or irradiat\$4 or illuminat\$4) and develop\$4 and (etch\$4 or remov\$4) and (plat\$4 or electroplat\$4) and (phenolic same (monomer\$5 near9 unit)) and undercut\$4 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |
| 29 | 1 | 430/322.ccls. and (((substrate or wafer or workpiece or platen) near16 (barrier or protective ARC or antireflect\$4 or BARC or poly\$3phenol\$4)) same (resist or photoresist or photosensitive or photocur\$3 or (radiation near9 sensitive))) and (adhes\$4 same (polyphenol\$4 near22 polymer\$4 near19 monomer\$4)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |
| 30 | 1 | 430/320.ccls. and ((substrate or wafer) same (barrier or layer or coat\$4 or film) same ((polyphenol\$4 near6 polymer\$4) or novolac) same (resist or photoresist or photosensitive)) and (expos\$4 or irradiat\$4 or illuminat\$4) and develop\$4 and (etch\$4 or remov\$4) and (plat\$4 or electroplat\$4) and (phenolic same (monomer\$5 near9 unit)) and undercut\$4 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |

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| 31 | 0 | 430/311.ccls. and ((substrate or wafer) same (barrier or layer or coat\$4 or film) same ((polyphenol\$4 near6 polymer\$4) or novolac) same (resist or photoresist or photosensitive)) and (expos\$4 or irradiat\$4 or illuminat\$4) and develop\$4 and (etch\$4 or remov\$4) and (plat\$4 or electroplat\$4) and (phenolic same (monomer\$5 near9 unit)) and undercut\$4 | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |
| 32 | 1 | ((substrate or wafer) same (barrier or layer or coat\$4 or film) same ((polyphenol\$4 near6 polymer\$4) or novolac) same (resist or photoresist or photosensitive)) and (expos\$4 or irradiat\$4 or illuminat\$4) and develop\$4 and (etch\$4 or remov\$4) and (plat\$4 or electroplat\$4) and (phenolic same (monomer\$5 near9 unit)) and undercut\$4 | US-PGPUB |
| 33 | 1 | ((substrate or wafer) same (barrier or layer or coat\$4 or film) same ((polyphenol\$4 near6 polymer\$4) or novolac) same (resist or photoresist or photosensitive)) and (expos\$4 or irradiat\$4 or illuminat\$4) and develop\$4 and (etch\$4 or remov\$4) and (plat\$4 or electroplat\$4) and (phenolic same (monomer\$5 near9 unit)) and undercut\$4 | US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB |

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|----|------|---|---|
| 34 | 0 | 430/313.ccls. and (((substrate or wafer or workpiece or platen) near16 (barrier or protective ARC or antireflect\$4 or BARC or poly\$3phenol\$4)) same (resist or photoresist or photosensitive or photocur\$3 or (radiation near9 sensitive))) and (adhes\$4 same (polyphenol\$4 near22 polymer\$4 near19 monomer\$4)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |